

IN THE CLAIMS

Please amend the claims as follows:

Claims 1-2 (Canceled).

Claim 3 (Previously Presented) A cleaning apparatus for cleaning exhaust gas coming from a production apparatus for producing a gallium nitride film semiconductor by subjecting gallium chloride gas as a gallium source which is generated through the circulation of hydrogen chloride gas over metallic gallium to vapor phase deposition through the reaction with ammonia so as to form a gallium nitride film, wherein an electroconductive corrosion-resistant material is used as the constructional material for introduction piping, and said introduction piping is electrically grounded.

Claim 4 (Canceled).

Claim 5 (Currently Amended) The cleaning apparatus according to ~~Claim~~claim 3, wherein the cleaning apparatus is a wet absorptive cleaning apparatus.

Claims 6-8 (Canceled).

Claim 9 (New) The cleaning apparatus of claim 3, wherein the cleaning apparatus is wet absorptive.

Claim 10 (New) The cleaning apparatus according to claim 3, further comprising:
detecting means for sampling exhaust gas circulating in the cleaning apparatus and
detecting oxygen or measuring a concentration of oxygen therein.

Claim 11 (New) The cleaning apparatus according to claim 3, wherein the electroconductive corrosion-resistant material is selected from the group consisting of stainless steel, and high nickel steel.

Claim 12 (New) The cleaning apparatus according to claim 3, wherein the electroconductive corrosion-resistant material is selected from the group consisting of an electroconductive resin and a metallic material coated with an electroconductive resin.

Claim 13 (New) The cleaning apparatus according to claim 12, wherein a specific volume resistivity of said electroconductive corrosion-resistant material is approximately $100 \Omega \text{ cm}$.

Claim 14 (New) The cleaning apparatus according to claim 3, wherein a specific volume resistivity of said electroconductive corrosion-resistant material is at most $1 \times 10^9 \Omega \text{ cm}$.

Claim 15 (New) The cleaning apparatus according to claim 14, wherein the specific volume resistivity is at most $1 \times 10^7 \Omega \text{ cm}$.